40/580560 1AP20 Rec'd PCT/PTO 26 MAY 2006

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q95169

Koji KUDO, et al.

Appln. No.: Not yet assigned

Confirmation No.: Not yet assigned Group Art Unit: Not yet assigned

Filed: May 26, 2006 Examiner: Not yet assigned

For: DISTRIBUTED-FEEDBACK SEMICONDUCTOR LASER, DISTRIBUTED-

FEEDBACK SEMICONDUCTOR LASER ARRAY, AND OPTICAL MODULE

INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. §§ 1.97 and 1.98

MAIL STOP AMENDMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

In accordance with the duty of disclosure under 37 C.F.R. § 1.56, Applicant hereby notifies the U.S. Patent and Trademark Office of the documents which are listed on the attached PTO/SB/08 A & B (modified) form and listed herein and which the Examiner may deem material to patentability of the claims of the above-identified application.

- M Aoki et al. "85°C 100Gbit/s Opeartion of 1.3-μm InGaA1As MQW-DFP Laser", ECOC2000 Col. 1, pp. 123-124.
- K. Nakahara et al., "115°C, 12-5Gb/s Direct Modulation of 1.3-μm InGaAlAs-MQW RWG DFB Laser with Notch-Free Grating Structure for Datacom Applications", OFC2003 PDP40.

INFORMATION DISCLOSURE STATEMENT New U.S. National Stage Entry of PCT/JP2001/016838

- 3. G. Shtengel et al., "High-speed Vertical-Cavity Surface Emitting Laser", IEEE Photonic Technology Letters, 1993, vo. 5, no. 12, pp. 1359-1362.
- A. Ramakrishnan et al., "Electrically Pumped 10 Gbit/s MOVPE-Grown
 Monolithic 1.3μm VCSEL with GaInNAs Active Region", IEE Electronic Letters,
 2002, Vol. 38, No. 7.
- M. Uchida et al., "An AlGaAs Laser with High-Quality Dry Etched Mirrors
 Fabricated Using an Ultrahigh Vacuum in Situ Dry Etching and Deposition
 Processing System", IEEE Journal of Quantum Electronic, 1998, vol. 24, no. 11, pp. 2170-2176.
- T. Yuasa et al., "Performance of Dry-Etched Short Cavity GaAs/AlGaAs
 Multiquantum-Well Lasers", Journal of Applied Physics, 1998, vol. 63, no. 5,
 pp.1321-1327.
- 7. T. Aoyagi et al., "Recent Progress of 10Gb/s Laser Diodes for Metropolitan Area Networks", SPIE, 2001, vol. 4580, APOC 2001, Beijing, China.
- 8. Y. Itaya et al., "Low Threshold Current GaInAsP/InO DFB Lasers, " IEEE Journal of Quantum Electronics, Vol. QE-23, No. 6, June 1987, pp. 828-834.
- 9. United States Patent No. 4,740,987, issued April 26, 1988.
- 10. United States Patent No. 4,796,273, issued January 3, 1989.
- United States Patent Application Publication No. 2003/0021319, published
 January 30, 2003.
- 12. Japanese Patent Publication No. 63-80590, published April 11, 1988.
- 13. Japanese Patent Publication No. 3-283483, published December 13, 1991.

INFORMATION DISCLOSURE STATEMENT

New U.S. National Stage Entry of PCT/JP2001/016838

- 14. Japanese Patent Publication No. 62-112391, published May 23, 1987.
- 15. Japanese Patent Publication No. 2002-198611, published July 12, 2002.
- United States Patent Application Publication No. 2002-0159705, published
 October 31, 2002.
- 17. Japanese Patent Publication No. 63-62390, published March 18, 1988.
- 18. Japanese Patent Publication No. 8-186334, published July 16, 1996.
- 19. Japanese Patent Publication No. 2624140, published April 11, 1997.
- 20. Japanese Patent Publication No. 2003-46190, February 14, 2003 (corresponds to U.S. Patent No. 6,888,869).
- 21. Japanese Patent Publication No. 2545994, published August 8, 1996.

One copy of each of the listed documents is submitted herewith.

The present Information Disclosure Statement is being filed: (1) No later than three months from the application's filing date; (2) Before the mailing date of the first Office Action on the merits (whichever is later); or (3) Before the mailing date of the first Office Action after filing a request for continued examination (RCE) under §1.114, and therefore, no Statement under 37 C.F.R. § 1.97(e) or fee under 37 C.F.R. § 1.17(p) is required.

In compliance with the concise explanation requirement under 37 C.F.R. § 1.98(a)(3) for foreign language documents, Applicant states that the listed references are either cited in the International Search Report of within the specification.

The submission of the listed documents is not intended as an admission that any such document constitutes prior art against the claims of the present application. Applicant does not

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waive any right to take any action that would be appropriate to antedate or otherwise remove any listed document as a competent reference against the claims of the present application.

The USPTO is directed and authorized to charge all required fees, except for the Issue Fee and the Publication Fee, to Deposit Account No. 19-4880. Please also credit any overpayments to said Deposit Account.

Respectfully submitted,

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Date: May 26, 2006

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MODIFIED PTO/SB/08 A & B (08-03)

Substitute for Form 1449 A & B/PTO			Complete if Known, EOOE & Co			
			Application Number	Note the signed OU OU		
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)			HDF	Confirmation Number	Not yet assigned	
				Filing Date	May 26, 2006	
			ANI	First Named Inventor	Koji KUDO	
			ry)	Art Unit	Not yet assigned	
				Examiner Name	Not yet assigned	
Sheet	1	of	2	Attorney Docket Number	Q95169	

U.S. PATENT DOCUMENTS						
Examiner Cite Initials* No.1	Cia	Document N	umber	Publication Date MM-DD-YYYY		
		Number	Kind Code ² (if known)		Name of Patentee or Applicant of Cited Document	
		US 4,470,987	Α	04-26-1988	McCall et al.	
		US 4,796,273	Α	01-03-1989	Yamaguchi	
		US 2003/0021319	A1	01-30-2003	Aoki	
		US 2002/0159705	A1	10-31-2002	Naniwae	

FOREIGN PATENT DOCUMENTS							
Examiner Cite Initials* No. ¹	Foreign Patent Document			Publication Date	Name of Patentee or		
	Country Code ³	Number ⁴	Kind Code ⁵ (if known)	MM-DD-YYYY	Applicant of Cited Document	Translation ⁶	
		JP	63-80590		04-11-1988		
		JP	3-283483		12-13-1991		
1		JР	62-112391		05-23-1987		
-		JР	2002-198311		10-31-2002		
		JP	63-62390		03-18-1988		
		JP	8-186334		07-16-1996		
		JP .	2624140		04-11-1997		
		JР	2003-46190		02-14-2003		
		JP	254994		08-08-1996		

NON PATENT LITERATURE DOCUMENTS						
Examiner Cite Initials* No.1		Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city, and/or country where published.				
		M Aoki et al. "85°C - 100Gbit/s Opeartion of 1.3-μm InGaA1As MQW-DFP Laser", ECOC2000 Col. 1, pp. 123-124.				
		K. Nakahara et al., "115°C, 12-5Gb/s Direct Modulation of 1.3-μm InGaAlAs-MQW RWG DFB Laser with Notch-Free Grating Structure for Datacom Applications", OFC2003 PDP40.				
		G. Shtengel et al., "High-speed Vertical-Cavity Surface Emitting Laser", IEEE Photonic Technology Letters, 1993, vo. 5, no. 12, pp. 1359-1362.				
		A. Ramakrishnan et al., "Electrically Pumped 10 Gbit/s MOVPE-Grown Monolithic 1.3µm VCSEL with GaInNAs Active Region", IEE Electronic Letters, 2002, Vol. 38, No. 7.				
		M. Uchida et al., "An AlGaAs Laser with High-Quality Dry Etched Mirrors Fabricated Using an Ultrahigh Vacuum in Situ Dry Etching and Deposition Processing System", IEEE Journal of Quantum Electronic, 1998, vol. 24, no. 11, pp. 2170-2176.				
		Y. Itaya et al., "Low Threshold Current GaInAsP/InO DFB Lasers, " IEEE Journal of Quantum Electronics, Vol. QE-23, No. 6, June 1987, pp. 828-834				
		T. Aoyagi et al., "Recent Progress of 10Gb/s Laser Diodes for Metropolitan Area Networks", SPIE, 2001, vol. 4580, APOC 2001, Beijing, China.				
		T. Yuasa et al., "Performance of Dry-Etched Short Cavity GaAs/AlGaAs Multiquantum-Well Lasers", Journal of Applied Physics, 1998, vol. 63, no. 5, pp. 1321-1327.				

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Examiner Signature	Date Considered	

^{*}EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹Applicant's unique citation designation number (optional). ²See Kind Codes of USPTO Patent Documents at www.uspto.gov, MPEP 901.04 or follow the hyperlink from the title of the document to the intranet. ³ Enter Office that issued the document, by the two-letter code (WIPO Standard ST. 3). ⁴For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁶ Applicant is to indicate here if English language Translation is attached.